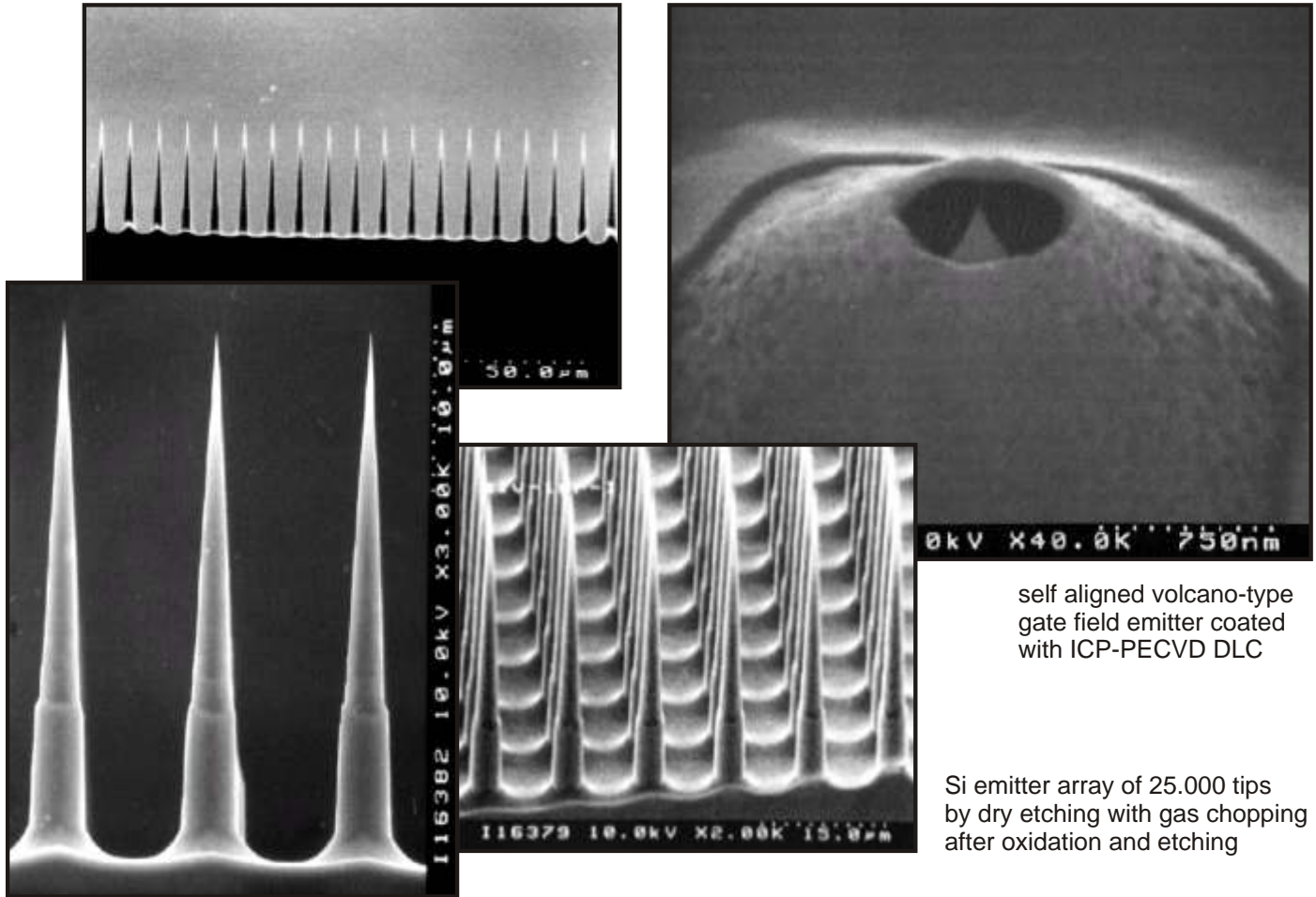


Plasmalab Data

ultrasharp Si tips by ICP etching for field emission arrays



self aligned volcano-type gate field emitter coated with ICP-PECVD DLC

Si emitter array of 25.000 tips by dry etching with gas chopping after oxidation and etching

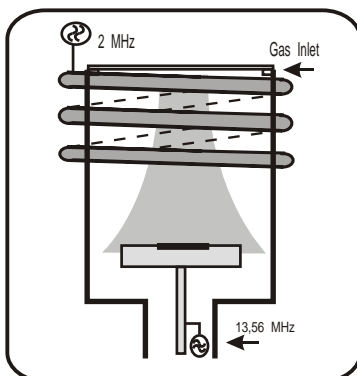
etched at - 50° C using gas chopping
tip radii of 2 - 10 nm possible
after oxidation sharpening

Courtesy of University of Kassel, Institute of Technical Physics, Dr. I. Rangelow

Plasmalab System 100

Plasmalab System 133

Plasmalab 80 Plus



Technology:
Reactive Ion Etching
Inductive Coupled Plasma Source
He backside cooling

